## FORM PTO-1449 (MODIFIED)

LIST OF PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT

Applicant(s): Allen et al. Docket No.: YOR92003 YOR920030175US1

Serial No.: 10/661,041

September 12, 2003 Filing Date:

Group: 2811

		J	J.S. PATENT DOCUMENTS		
EXAMINER INITIAL	DOCUMENT NO.	DATE	NAME	CLASS/SUBCLASS	FILING DATE  IF APPROPRIATE
a	5,753,418	05/19/98	Tsai et al.	430/313	
av	6,009,888	01/04/00	Ye et al.	134/1.3	
Cr.	6,316,167	11/13/01	Angelopoulos et al.	430/313	
on	6,387,798	05/14/02	Loke et al.	438/623	
<u>a</u>	6,514,867	02/04/03	Hui et al.	438/713	
		FOR	EIGN PATENT DOCUMENTS	-	
EXAMINER INITIAL	DOCUMENT NO.	DATE	COUNTRY	CLASS/SUBCLASS	TRANSLATION YES NO
	EP 0 236 220 A1	13/04/88	Europe		
			OTHER DOCUMENTS		
EXAMINER INITIAL	REF NO. AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.				
	Celii et al., "Process Characterization for Tapered Contact Etch," J. Vac. Sci. Technol. B 19(5), American Vacuum Society, Pgs. 1845-1851 (Sept/Oct 2001).  Mahorowala et al., "Tunable Anti-Reflective Coatings with Built-In Hard Mask Properties Facilitating Thin Resist Processing," Proceedings of the SPIE, Vol. 4343, Pgs. 306-316 (2001).				

Date Considered Examiner

Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.